## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

## PATENT APPLICATION

Applicant: Nallan, et al. Case: 7017C1/ETCH/METAL-NVM/JB

Serial No.: 10/805,890 Filed: March 22, 2004

Examiner: Tran, Binh X Group Art Unit: 1765

Confirmation No.: 1896

Title: METHOD OF PLASMA ETCHING OF HIGH-K DIELECTRIC MATERIALS WITH

HIGH SELECTIVITY TO UNDERLYING LAYERS

Mail Stop Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450.

SIR:

## RESPONSE TO OFFICE ACTION DATED APRIL 17, 2006

In response to the Office Action dated April 17, 2006, having a statutory period for response set to expire on July 17, 2006, please enter this response and reconsider the claims pending in the application for reasons discussed below. The Terminal Disclaimer fee under 37 C.F.R. §1.20(d) has been paid on-line at the Patent Office Electronic Business Center. Although the Applicants believe that no other fees are due in connection with this response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782 for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.